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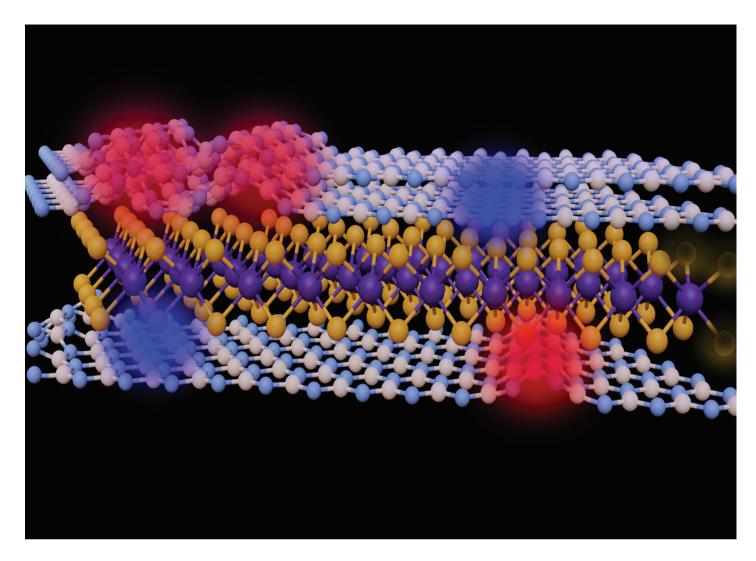
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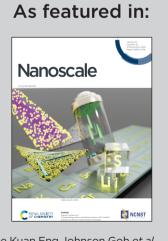




Showcasing work from Professor Kuan Eng Johnson Goh's group at Institute of Materials Research and Engineering (IMRE), Agency for Science, Technology and Research (A*STAR), Singapore.

Probing charge traps at the 2D semiconductor/dielectric interface

Conventional techniques for investigating charge traps at the traditional bulk-semiconductor/dielectric interface are not fully compatible with 2D material-based devices. We review the pros and cons of these techniques to provide guidance for their suitability/limitations in analysing charge traps and quantifying the density of interface traps at the 2D semiconductor/dielectric interface.



See Kuan Eng Johnson Goh *et al., Nanoscale*, 2023, **15**, 16818.

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